

Determination of Bi positions in GaAs<sub>(1-x)</sub>Bi<sub>x</sub> heterostructures with atomic column resolution



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M.F. Chisholm







#### I. Introduction

- Framework
- Tools
- Previous GaAsBi works
- Motivation

### II. Methodology & Materials

- Growth
- HAADF
- Image processing
- Results
- V. Image simulation

# Transmission electron microscopes













# Previous TEM work in GaAsBi

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# Molecular beam epitaxy of GaAsBi on (311)B GaAs substrates



(001)

(311)B

M. Henini et al. Appl. Phys. Lett. 91, 251909 2007



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# Previous TEM work in GaAsBi

#### J. F. Rodrigo et al. Applied Surface Science 256 (2010) 5688-5690

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1.0 1.2 1.4 Energy (eV)

Fig. 1. Bright field TEM images, diffraction patterns and photoluminescence spectra of the as grown sample S1 (a, b and c) and annealed sample S2 (d, e and f). Scale bar corresponds to 500 nm.





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# • Focussed Ion Beam

#### FEI DUAL BEAM FEI QUANTA 200 3D

- Nano-machinning
- -3D sample preparation for tomopraphy of localized areas.
- Substrates nano-patterning
- As ions imaging
- -3D tomography









I. Introduction

# **The Motivation**



Spatial correlation between Bi atoms in dilute GaAs<sub>1-x</sub>Bi<sub>x</sub>: From random distribution to Bi pairing and clustering

G. Ciatto, 1,\* E. C. Young, 2 F. Glas, 3 J. Chen, 4 R. Alonso Mori, 4 and T. Tiedje2

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# Methodology and materials



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#### Methodology & Materials The sample Universidad de Cádiz I. Introduction Framework • Tools $p_{Bi} = 1.2 \cdot 10^{-7}$ Torr • Previous [001] GaBi<sub>x</sub>As<sub>(1-)</sub> GaAsBi works $p_{As} = 8.0.10^{-6}$ Torr 1 µm Motivation T ≈ 350°C II. Methodology & Materials • Growth • HAADF The University of Nottingham GaAs Substrate • Image processing semi-insulating (100) Results V. Image simulation Region of near stochiometric growth HRXRD $\longrightarrow$ x $\approx$ 0.03 Henini et al. APL 91, 251909 (2007)

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## Short acquisition time

(1 image in less than 16 s)

Proportionality Intensity-Atomic number



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# Why HAADF?

- For a ternary alloy:
  - Linear relationship

Intensity quotient (R) vs. Composition.





Column-by-column compositional mapping by Z-contrast imaging S. I. Molina et al. Ultramicroscopy 109 (2009) 172–176

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## **Quantitative Compositional analysis** HAADF EELS



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- Localize intensity maxima (As/Bi columns) Localize Ga columns
- 2.
- 3. Select integration area
- Determine average integrated intensity in every 4. dumbbell: I<sub>Ga</sub> and I<sub>As/Bi</sub>





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# Image processing Determining *R* factors:





Minimize variations due to:

- Same local thickness
- Same amorphous layer
- Same experimental image conditions





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# Plotting R







# Universidad de Cádiz

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# • In order to relate *R* with *x* (Bi content):

Analysis



N, the number of atomic columns,  $x_i = Bi$  percentage per column,  $\Sigma x_i = 2.65\%$  total Bi percentage

# • Fitting equation:

R = 1.0629 + 0.0729x

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Results



# **Results**

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# The next step...

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Solving the Schrödinger stationary equation

$$\frac{\hbar^2}{2m_0}\Delta |\Psi\rangle + [E_t - \hat{V}]|\Psi\rangle = 0$$

by FFT multislice method (Ishizuka's code)

STEM image simulations



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# The SICSTEM software A Paralell HAADF-STEM Simulation Sw





# Cádiz University supercomputer

- Hewlett-Packard (2007)
  - 320 Xeon Woodcrest cores running at 3GHz
  - 3.75 Tflops (position 327 in Top500 last year)
  - Each node 8 or 16 Gb
     RAM
  - Total RAM = 700 GB
  - 2.5 TB disk capacity

### **Image Simulations**

Ga

As

Bi



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# Create the supercell

- 56,000 atoms
- 5x6x40 nm









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# Aprox. time for simulation: 50 hours. High resolution: 182 pix/nm

# **Phase-grating Parallelism**



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### GaAsBi 40 nm - 3 Bi Atoms in red





# **Summary and Conclusions**



# ¡Muchas gracias!

Cádiz old town.

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